

## Supplementary information: Fabrication of monolithic 3D micro-systems

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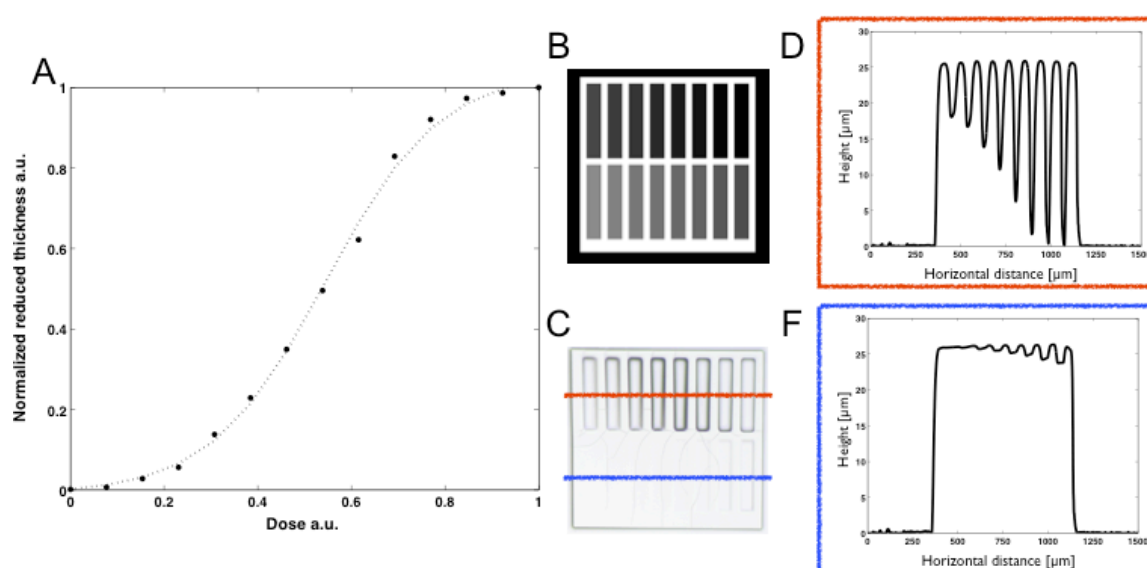


Fig. S11. (A) Thickness of SU-8 (10) vs. exposure dose measured with a Dektak 6M profilometer. (B) Illuminating pattern used for the calibration. (C) SU-8 created with illuminating pattern in B. (D) Profile measured along the red line in C. (E) Profile measured along the blue line in C.

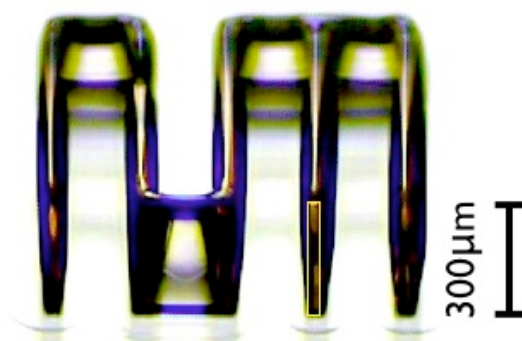


Fig. S12. SU-8/S1818 structure, showing a 10:1 aspect ratio.

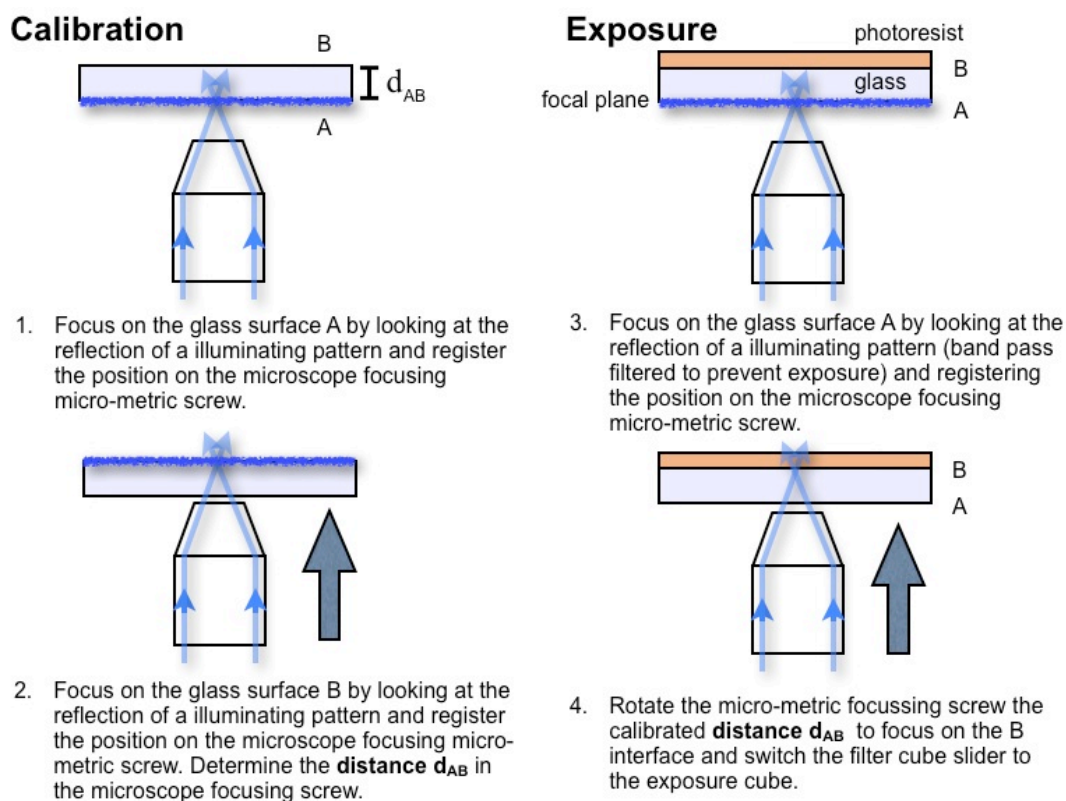


Fig. SI3. Procedure used to focus the exposure pattern at the glass-photos resist interface. The micrometric focusing screw is calibrated with the distance  $d_{AB}$  corresponding to the glass slide thickness (steps 1 and 2). 3) The focal position at the free glass surface of a spin coated glass slide is determined using band pass filtered illumination to prevent the photoresist exposure. 4) The focusing screw is rotated in the calibrated distance  $d_{AB}$ , thus moving the focus to the glass-photos resist interface. The filter cube slider is switched to the exposure position.